

ABSTRACT OF THE DISCLOSURE

*Suba!* An exposure apparatus includes an illumination optical system for illuminating an original with ultraviolet light, a projection optical system for projecting a pattern of the original onto a substrate to be exposed, and a gas purging device for replacing an inside space, where optical components of at least one of the illumination optical system and the projection optical system are placed, with a gas containing substantially no water content or an inert gas.

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